

Appl. No. 10/044,271

Amdt. Dated Jun. 23, 2005

Reply to Office Action of Mar. 23, 2005

Amendments to the Abstract:

Please amend the abstract as follows:

~~Methods A method for making thin film filters having a negative temperature drift coefficient are the subject of the present invention. Such filters can achieve better optical control within an operational temperature range from [[-5]] -5°C to 70°C degrees centigrade.~~ A first embodiment of the present invention includes the steps of: 1. providing a substrate wafer which has a coefficient of thermal expansion (CTE) greater than that of a selected film stack material; 2. polishing the substrate wafer; 3. depositing thin film layers made of the film stack material on the substrate wafer at a temperature substantially higher than room temperature; 4. cooling the substrate-film stack laminate to room temperature, thus forming a convex-shaped laminate; 5. cutting the cooled laminate into pieces. A second embodiment includes the steps of: 1. providing a laminate ~~comprise~~ composed of a glass substrate and a film stack; 2. using at least one ion beam source to bombard the film stack of the laminate with high energy ions; 3. cutting the bombarded laminate into pieces.